

US DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

APPLICANT: MARTIN RICHARDSON
FOR: EUV, XUV, AND X-RAY WAVELENGTH SOURCES CREATED FROM LASER PLASMA
PRODUCED FROM LIQUID METAL SOLUTIONS

LIST OF ART CITED BY APPLICANT

U.S. PATENT DOCUMENTS

EXAMINER	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
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AB	4,328,464	05/04/82	Pivrotto	330	4.3	02/07/80
AC	4,700,371	10/13/87	Forsyth et al.	378	34	11/08/84
AD	4,723,262	02/02/88	Noda et al.	378	119	12/26/85
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AF	4,953,191	08/28/90	Smither et al.	378	143	07/24/89
AG	5,126,755	06/30/92	Sharpe et al.	346	75	03/26/91
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AI	5,148,462	09/15/92	Spitsyn et al.	378	143	04/08/91
AJ	5,151,928	09/29/92	Hirose	378	119	08/20/91
AK	5,243,638	09/07/93	Wang et al.	378	119	03/10/92
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OTHER ART (Including Author, Title, Date, Pertinent Pages. Etc.)

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OB T. Mochizuki, *SOFT X-RAY OPTICS AND TECHNOLOGY*, Proceedings Of SPIE-The International Society For Optical Engineering, Vol. 733, P. 23-27, December 1986

OC Martin Richardson, *LASER PLASMA SOURCE FOR X-RAY PROJECTION LITHOGRAPHY*, Laser-Induced Damage In Optical Materials, Vol. 1848, P. 483-500, 1992

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